| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|---|---|---|---|---|---|---|
| L1 | 49 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and anodic near5 dissolution and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 15:40 |
| L2 | 34 | L1 and wafer | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 15:38 |
| L3 | 48 | L1 and rate | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 15:38 |
| L4 | 34 | L1 and wafer and rate | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 15:40 |
| L5 | 1 | L1 and wafer and rate near5 electropolish$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 15:40 |
| L6 | 6 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and wafer and rate near5 electropolish$3 and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 15:53 |
| L7 | 36 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) near5 rate and electropolish$3 and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 15:47 |

| L8 | 6 | (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and wafer and rate near5 electropolish$3 and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 15:53 |
|---|---|---|---|---|---|---|
| S2 | 108 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and electropolish$3 and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/13 12:44 |
| S3 | 58 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and electropolish$3 and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) and leveler | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/09 17:40 |
| S4 | 118 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and anodic and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) and leveler | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/09 17:41 |
| S5 | 27 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and anodic near5 dissolution and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) and leveler | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/09 17:48 |
| S6 | 49 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and anodic near5 dissolution and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/14 14:53 |
| S7 | 22 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and anodic near5 dissolution and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) not S5 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/09 17:50 |

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| S8 | 10 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and electrodissolution and (surfactant wetting carrier suppressor suppresser) and (brighten$4 accelerator) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/09 17:51 |
| S9 | 905 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and electropolish$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/13 11:31 |
| S10 | 611 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and electropolish$3 and (trench microvia recess$3 "through-hole" "thru-hole" opening hole via) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/13 12:45 |
| S11 | 464 | ·("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and electropolish$3 and (trench microvia recess$3 "through-hole" "thru-hole" opening hole via) and copper | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/13 12:45 |
| S12 | 99 | ("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 electrodeposit$5 electroplat$5) and electropolish$3 and (trench microvia recess$3 "through-hole" "thru-hole" opening hole via) and copper and (((zero off pause) near5 (current)) ((off relaxation rest) near5 time) ((off relaxation) near5 period) (zero · near5 pulse) ) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/13 12:46 |